



IFW

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q77434

Tsutomu SHOKI

Appln. No.: 10/658,372

Group Art Unit: 1756

Confirmation No.: 3326

Examiner: John S. Ruggles

Filed: September 10, 2003

For: METHOD OF PRODUCING A REFLECTION TYPE MASK BLANK, METHOD OF PRODUCING A REFLECTION TYPE MASK, AND METHOD OF PRODUCING A SEMICONDUCTOR DEVICE

**RESPONSE TO RESTRICTION REQUIREMENT**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated January 10, 2006, please consider the remarks as submitted herewith on the accompanying pages.